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- (71) **Applicant (for all designated States except US):** Ricoh Company, Ltd. [JP/JP]; 3-6, Nakamagome 1-chome, Ohta-ku, Tokyo, 1438555 (JP).
- (72) **Inventor; and**
- (71) **Applicant (for US only):** HIRAOKA, Takao [JP/JP]; c/o Ricoh Company, Ltd., 3-6, Nakamagome 1-chome, Ohta-ku, Tokyo, 1438555 (JP).
- (74) **Agent:** HIROTA, Koichi; HIROTA, NAGARE & ASSOCIATES, 4th Floor, TS Bldg., 1-24-10, Yoyogi, Shibuya-ku, Tokyo, 1510053 (JP).

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(54) **Title:** PHOTOPOLYMERIZABLE INKJET INK

(57) **Abstract:** To provide a photopolymerizable inkjet ink, which contains photopolymerizable monomers containing at least one selected from the following compound group (A) compounds of which are negative for skin sensitization, and at least one selected from the following compound group (B) compounds of which are negative for skin sensitization, wherein the compound group (A) is a compound group consisting of caprolactone-modified dipentaerythritol hexaacrylate, polyethoxylated tetramethylol methane tetraacrylate, ethylene oxide-modified bisphenol A diacrylate, caprolactone-modified hydroxy pivalic acid neopentyl glycol diacrylate, polypropylene glycol diacrylate [$\text{CH}_2=\text{CH}-\text{CO}-(\text{OC}_3\text{H}_6)_n-\text{OCOCH}=\text{CH}_2$ ($n \approx 12$)], hydroxyethyl acryl amide, trimethylol propane trimethacrylate, and tricyclodecane dimethanol dimethacrylate, and the compound group (B) is a compound group consisting of ethylene oxide-modified phenolacrylate, isostearyl acrylate, ethylene oxide-modified trimethylol propane trimethacrylate, stearyl methacrylate, and glycerin dimethacrylate.

